	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
1	BRS	L1	3	(cmp or "chemical mechanical polishing") same iminodiacetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 08:45			0
2	BRS	L8	3	(cmp or "chemical mechanical polishing" same polish$3) same iminodiacetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 08:46			0
3	BRS	L15	11	(cmp or "chemical mechanical polishing" or polish$3 or planariz$5) same iminodiacetic	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 09:52			0
4	BRS	L22	655	(cmp or "chemical mechanical polishing" or polish$3 or planariz$5) same (PVA or "polyvinyl alcohol" or "polyethylene oxide" or "polypropylene oxide" or "sulfonate polymer" or "sulfonic acid polymer")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:06			0
5	BRS	L29	461	22 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:06			0
6	BRS	L36	40	22 same semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 09:59			0
7	BRS	L43	14	36 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:07			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
8	BRS	L50	9	29 and 438/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:07			0
9	BRS	L57	21	29 and 252/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:07			0
10	BRS	L71	21	57 and 252/$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:10			0
11	BRS	L64	9	50 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:10			0
12	BRS	L78	19	71 not 64	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 10:13			0
13	BRS	L92	11	(cmp or "chemical mechanical polishing" or polish$3 or planariz$5) same (iminodiacetic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:50			0
14	BRS	L99	40	(abrasive or slurry) same (iminodiacetic)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:50			0

	Type	L #	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Errors
15	BRS	L106	22	99 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:52			0
16	BRS	L113	55	(abrasive or slurry) same (iminodiacetic or ida)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:50			0
17	BRS	L120	22	(cmp or "chemical mechanical polishing" or polish$3 or planariz$5) same (iminodiacetic or ida)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:51			0
18	BRS	L127	8	120 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:51			0
19	BRS	L134	35	113 and @pd<=19990810	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/06/12 13:53			0